

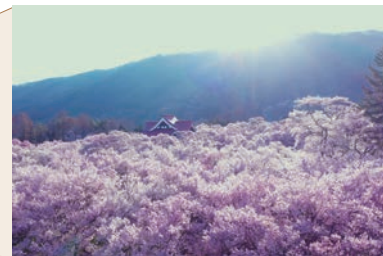
Photomask Japan 2021 Digital Forum

April 20 (Tue.) - 21 (Wed.), 2021

Considering the ongoing situation of COVID-19, we have concluded we will not be able to take sufficient safety measures at an in-person symposium. Photomask Japan 2021 will be held fully online on April 20-21. We appreciate your understanding.



You can also enjoy
PMJ movies and
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The 27th Symposium on Photomask and Next Generation Lithography Mask Technology

Abstract Due Date: November 30 (Mon.), 2020
* Camera-Ready Abstract Submission is not required.
Manuscript Due Date: March 31 (Wed.), 2021
These are **FIRM!**
Manuscripts are required of all accepted applicants and must be submitted in English.

Symposium Chair: Prof. Takeo Watanabe, University of Hyogo (Japan)
Organized by Photomask Japan and SPIE, Co-organized by BACUS and EMLC

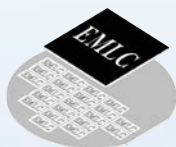
Papers are solicited on the following and related topics:

- Materials for photomasks
- Fabrication process steps and equipment for photomasks (developing, etching, cleaning etc.)
- Photomask writing tools and technologies including multi-beam EB writer
- Tools and technologies for metrology/ inspection/ repair
- Technologies and Infrastructures for EUVL/ NIL/ FPD masks
- EDA, MDP, curvilinear ILT and DTCO
- Photomasks with RET: PSM, OPC, SMO and multiple patterning
- Photomask-related lithography technologies
- NGL mask technologies and their applications: DSA and others
- Strategy and business challenges: cost, cycle time and total mask solutions
- Patterning technologies for semiconductor and electronic devices
- Semiconductor manufacturing technologies
- eBeam direct writing and eBeam lithography technologies
- Photomask and lithography related technologies in academia

Organized by



Co-organized by



Supported by



For more information, contact:

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<http://www.photomask-japan.org>

All abstracts are to be registered electronically via the PMJ website to get the qualification for abstract submission to the conference.

See the next page for more information ↓

SPIE Proceedings Coordinator
E-mail: joels@spie.org

PMJ Website will begin accepting abstracts: **October 1 (Thu.), 2020**

* **Abstract Due Date: November 30 (Mon.), 2020**

* **Manuscript Due Date: March 31 (Wed.), 2021**

Camera-Ready Abstract Submission is not required in PMJ2021.

Abstracts will be published in Digest of Paper, which will be available on the website.

All abstracts must be registered electronically with the PMJ website at: <http://www.photomask-japan.org>

If electronic submission is not possible then authors are asked to contact the Photomask Japan Secretariat before the abstract due date.

All authors are strongly encouraged to submit their abstract by November 30, 2020.

Please note : the electronic abstract submission system will close on time and late abstracts will not be accepted.

And Manuscripts are required of all accepted applicants and must be submitted in English.

Please note: This information is subject to change without notice. PMJ requests all prospective authors to regularly check the PMJ website for updates.

To submit an abstract:

Abstracts must be written and presented in **English**.

All abstracts must be registered electronically in a **PDF file** via the conference website. For registration information, please visit the PMJ website.

Abstract Submission Information:

<http://www.photomask-japan.org>

All abstracts must contain the following information:

1. Title of Abstract:

Title should be in bold font using both upper and lower case.

2. Names of All Authors:

Names should be grouped by affiliation, listing Principal Author first. Please include both family and given names.

3. Abstract and Figures:

Text should be approximately 250 words, not exceeding one A4 page including figures.

4. Keywords:

List maximum of five keywords. Please choose at least one keyword for your abstract.

Your Abstract Reference Number will be automatically sent to you via e-mail as soon as your application has been received through the web page. If you do not receive a response within 24 hours, please contact the Abstract Submission Office.

Sample Abstract Format:

(1) Title

(2) Complete Author List

E.g., Akihiko Ando (Kioxia Corporation, Japan),
Yosuke Kojima (Toppan Printing Co., Ltd., Japan),
Masaaki Koyama (Sony Semiconductor Manufacturing Corporation, Japan),
Tetsuo Harada (University of Hyogo, Japan)

(3) Abstract Text

(4) Keyword(s)

(1) and (2) should be centered on the page.

(2) Authors names should be spelled out completely.

(3) should be 250 words.

Notification of Acceptance:

The Photomask Japan Program Committee will review all contributed abstracts. Applicants will be notified of acceptance or rejection by e-mail no later than the end of January 2021.

Photomask and Lithography related Technology in Academia

PMJ offers an opportunity for university students or postdoctoral researchers to present their works on mask / lithography technology fields.

Those who wish to present their works are asked to submit an abstract in accordance with the PMJ call for papers.

Session Scope: Mask technology, lithography technology and applications

Object Presenter: Applicants should be university students or postdoctoral researchers

Registration Fee: Free for Academia

Digital Forum Operation (tentative)

Sessions:

- Oral session: Pre-recorded Video Presentation + Live Q&A (Q&A will be on live via the designated platform after each presentation.)
- Poster session: 5 minutes Short Presentation with PDF Material (On-demand only)

Presentation Materials:

- The detailed guidelines will be available later.

Abstract Submission Office:

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